

predict | test | monitor | measure | modify

Expand your process window with the NovaCentrix Controlled Environment Chuck EX-1. Designed for use with any PulseForge[®] 1200/1300 tools, the EX-1 allows sample processing beyond standard atmospheric conditions. Pre-heat samples up to 300°C or increase thermal transfer by cooling. A porous vacuum chuck minimizes thermal contact resistance and supports simple, repeatable sample placement. The EX-1 sealed chamber allows purging with N₂ or any other process gas. An external vacuum pump option is also available taking photonic curing into a vacuum environment. Take R&D to the next level with the NovaCentrix EX-1.

FEATURES

- Straightforward sample processing/alignment on porous vacuum chuck surface
- User-selectable controlled temperature range from 10°C to 300°C
- Removable hinged chamber lid with quartz window allows vacuum and pressurized processes
- Vacuum to 200mT and below with external vacuum pump option
- Designed for operation on existing PulseForge 1200/1300 tool sample tables
- Integrated bolometer holder for quick process checks

CHUCK CONFIGURATIONS

1. Base Controlled Environment Chuck
 - Temperature-controlled (10°- 300°) vacuum surface
2. Base Controlled Environment Chuck with Sealed Chamber*
 - Temperature-controlled (10°- 300°) vacuum surface
 - Pressurized or vacuum processing capability (*with user-supplied vacuum pump*)
3. Base Controlled Environment Chuck, Sealed Chamber*, and External Vacuum Pump
 - Temperature-controlled (10°- 300°) vacuum surface
 - Pressurized or vacuum processing (below 200 mT)

* Sealed Chamber available with two quartz window options based on expected use of the PulseForge tool:

- Fused Quartz - Suitable for PulseForge tool operation up to 500V
- Synthetic Fused Silica - For processing above 500V, fused silica preferred due to high UV transmittance

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